



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 9635**
Satoshi MAEMORI et al. : Attorney Docket No. 2001_1300A
Serial No. 09/955,111 : Group Art Unit 1752
Filed September 19, 2001 : Examiner Sin J. Lee

POSITIVE-WORKING PHOTORESIST
COMPOSITION AND PHOTSENSITIVE
MATERIAL USING SAME

Mail Stop: AF

RESPONSE TO FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Final Rejection dated September 7, 2005, the period for response having been extended for one month by the attached petition, please amend the present application as follows: